



Session Title:	[WeF1] Nano Thin Film Deposition III
Session Date:	November 13 (Wed.), 2024
Session Time:	09:00-10:40
Session Room:	Room F (Ballroom, 5F, Grand Josun Busan)
Session Chair:	Prof. Jeong Hwan Han (Seoul Nat'l Univ. of Science and Tech., Korea)

[WeF1-1] [Invited] **09:00-09:30**

Growth Inhibition of ZnS ALD by Atomic Layer Etching for Area Selective Deposition

Taewook Nam (Sejong Univ., Korea) and Steven M. George (Univ. of Colorado Boulder, USA)

[WeF1-2] [Invited] **09:30-09:55**

Atomic Layer Deposition Process and Its Application for Semiconductor Field

Woo-Jae Lee (Pukyong Nat'l Univ., Korea)

[WeF1-3] [Invited] **09:55-10:20**

Atomic-Layer-Deposition for the Advanced Technology

Van Quang Nguyen, Jae Bin Ahn, Jongho Kim, Kang Hun Cho, and Jihye Kim (ISAC Research Inc., Korea)

[WeF1-4] **10:20-10:40**

A New Plasma Source for ALD Process in Large Batch System

Jeonghee Jo, Kwanghyun Jin, Wooduck Jung, and Junjin Hyon (EUGENETECH, Korea)